

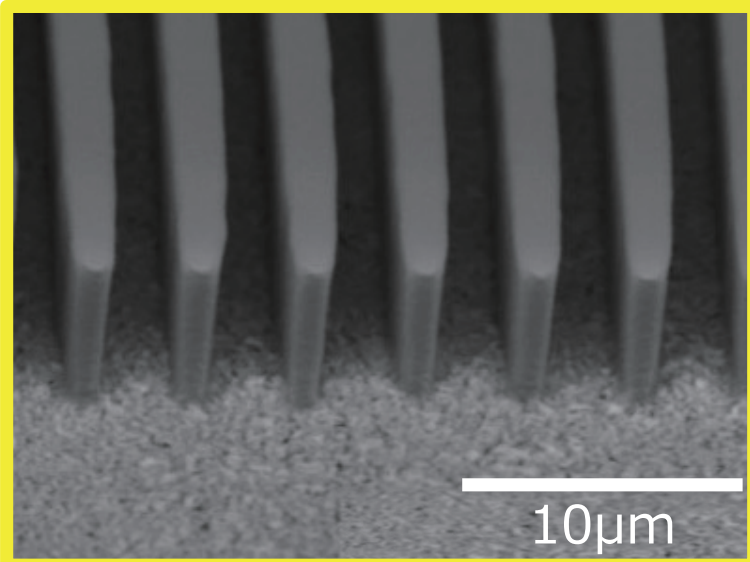
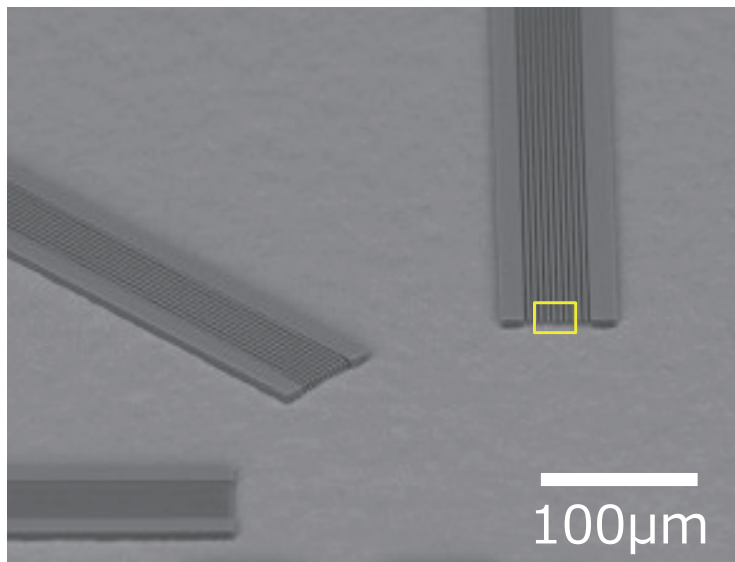
特許取得済

二流体現像機

Two-Fluid Spray Developer

最先端の精度：L/S=2/2 μ mを実現！

State-of-the-art technology: L/S=2/2 μ m !



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SAP/MSAPのファインパターン形成に寄与

Effective for fine pattern formation on SAP/MSAP

■ 現像液とエアを混合して噴射する二流体ノズルを採用

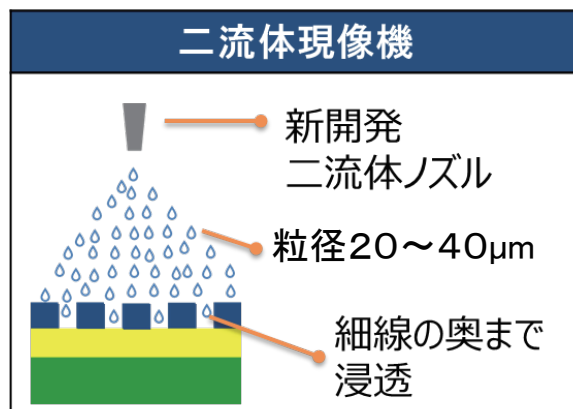
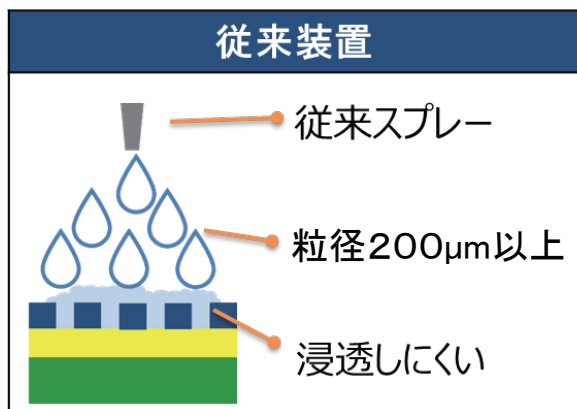
Two-fluid nozzles spraying mixture of air and liquid

■ 微小液滴が未現像やスカム残渣の抑制に効果を発揮！

Micro-droplets effectively suppress insufficient development and scum residues!

■ 微細回路形成の現像処理に最適

Suitable to development process of fine circuit formation



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